

PATENT

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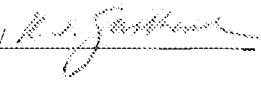
Applicants	Ishiduka, et al.	Examiner:	Johnson, Connie P.
Application No.:	10/591,718	Group Art Unit:	1795
Confirmation No:	3280	Docket:	1608-7 PCT/US/RCE II
Filed:	September 5, 2006	Dated:	April 1, 2010
For:	POSITIVE-TYPE RESIST COMPOSITION FOR LIQUID IMMERSION LITHOGRAPHY AND METHOD FOR FORMING RESIST PATTERN		

Commissioner for Patents
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Dated: April 1, 2010

Signature: K.J. Goodhand/ 

AMENDMENT AND RESPONSE PURSUANT TO 37 C.F.R. §1.114

Sir:

This is in response to the Office Action dated January 7, 2010, the due date for which is April 7, 2010. Please amend the above-identified application with the filing of a request for Continued Examination (RCE) as follows:

Amendments to the Claims begin on page 2 of this submission.

Remarks begin on page 9 of this submission.